

## EAST Search History

MT

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L4	1	(gate adj dielectric and spacer and epitaxial near thickening and silicide and source/drain near regions and (enriched same dopant)).CLM.	US-PGPUB; USPAT; USOCR; EPO; JPO	OR	OFF	2006/02/21 10:18